

ALD 2017 - 17th International Conference on Atomic Layer Deposition

Veranstaltung - ALD 2017 - 17th International Conference on Atomic Layer Deposition

Titel	ALD 2017 - 17th International Conference on Atomic Layer Deposition
Wann	Sa, 15. Juli 2017 - Di, 18. Juli 2017

Beschreibung

ALD 2017 - 17th International Conference on Atomic Layer Deposition - Featuring the Atomic Layer Etching Workshop -

DATE & LOCATION:

July 15-18, 2017 Sheraton Denver, Denver, Colorado

SCOPE:

ALD 2017 will be a three-day meeting (preceded by a one day tutorial), dedicated to the science and technology of atomic layer controlled deposition of thin films. Once again the meeting will feature the Atomic Layer Etching Workshop. As in past conferences, the presentations will follow an all-electronic format, and electronic copies of the presentations will available online.

WEBSITE:

Details will be posted to the ALD 2017 Website in November 2016.

www.ald-avs.org

Lokalität - Denver

Standort	Denver
Ortsname	Denver
Bundesland	Colorado
Land	US